

This is a repository copy of Aberration Corrected Transmission Electron Microscopy.

White Rose Research Online URL for this paper: http://eprints.whiterose.ac.uk/129401/

Version: Accepted Version

# Article:

Walther, T. orcid.org/0000-0003-3571-6263, Dunin-Borkowski, R.E., Rouviere, J.-L. et al. (1 more author) (2017) Aberration Corrected Transmission Electron Microscopy. Journal Of Materials Research, 32 (5). p. 911. ISSN 0884-2914

https://doi.org/10.1557/jmr.2017.74

## Reuse

Unless indicated otherwise, fulltext items are protected by copyright with all rights reserved. The copyright exception in section 29 of the Copyright, Designs and Patents Act 1988 allows the making of a single copy solely for the purpose of non-commercial research or private study within the limits of fair dealing. The publisher or other rights-holder may allow further reproduction and re-use of this version - refer to the White Rose Research Online record for this item. Where records identify the publisher as the copyright holder, users can verify any specific terms of use on the publisher's website.

### Takedown

If you consider content in White Rose Research Online to be in breach of UK law, please notify us by emailing eprints@whiterose.ac.uk including the URL of the record and the reason for the withdrawal request.



## ABERRATION CORRECTED TRANSMISSION ELECTRON MICROSCOPY

This focus issue of the Journal of Materials Research contains peer reviewed articles that were accepted in response to a call for manuscripts

#### Introduction

#### **Guest Editors:**

**Thomas Walther** University of Sheffield, United Kingdom

**Rafal E Dunin-Borkowski** Research Centre Jülich, Germany

**Jean-Luc Rouvière** CEA Grenoble, France

Eric A. Stach Brookhaven National Laboratory, USA

With the commercial availability of correctors for the spherical and chromatic aberrations of the imaging lenses in transmission and scanning transmission electron microscopes in the last 17 years, during which the focus has been mainly on installation, characterization, and testing, the focus now shifts towards new areas of science that can be addressed with this novel equipment.

The MRS meeting underpinning this Focus Issue has brought together researchers from different scientific fields to discuss their need for better resolved, faster, and more controlled experimental materials studies to be conducted in aberration corrected (scanning) transmission electron microscopes. This includes imaging, spectroscopy, and diffraction based applications to materials science problems with planar and focused illumination.

The papers collected in this issue have been written by a number of experts in the field. David J. Smith presents his work on semiconductor hetero-interfaces and semiconductor-perovskite interfaces and Ritesh Sachan et al., their overview of 3D ion track imaging in irradiated pyrochlore. Other topics discussed include recent progress made in measuring materials properties, such as crystallographic polarity (Roshko et al.), ionic displacement fields (Liu et al.), polarization (Tang et al.), segregation (Peter et al., Walther et al.) and strain within nano-scale regions (Norouzpour and Herring), with improved lateral resolution and precision.

We hope the readers will find this volume to be a useful collection of methodological papers representing the rapid advancement in this field. Finally, we are very grateful to both the authors and reviewers of the many high-quality manuscripts submitted to this JMR Focus Issue on Aberration corrected Transmission Electron Microscopy.

## ON THE COVER:

MBE grown GaN nanowire (NW) exhibiting a core-shell inversion domain boundary. The dark lines are AlN markers to understand how the NW grew during the MBE process. Imaged with probe-corrected Titan<sup>3</sup> Ultimate at 300 kV with 24 mrad convergence angle, 70 pA beam current, 2048<sup>2</sup> pixels with 11.8pm sampling, leading to 24.2x24.2 nm<sup>2</sup> field of view on an annular detector detecting from 55 mrad to around 200 mrad. (Image courtesy of Benedikt Haas, CEA Grenoble)